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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:	)	
Inventors: Joshi et al.	)	ATTORNEY FILE NO.: SLA0786
Serial No.: 10/812,591	)	
Filed: March 29, 2004	)	Examiner: Sarkar, Asok
Title: HIGH DENSITY PLASMA PROCESS FOR THE TRANS- FORMATION OF SILICON DIOXIDE ON SILICON CARBIDE SUBSTRATES	)	Customer No.: 55,286
	)	Group Art: 2891
	)	Confirmation No.: 2314

Mail Stop Amendments  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

## CERTIFICATION UNDER 37 CFR § 1.8

I hereby certify that this correspondence is being facsimile transmitted to the US Patent and Trademark Office, fax No. 571 273 8300, on this date 5/24/2006

Date

5/24/2006

Signature

RESPONSE UNDER 37 CFR 1.116

In response to an Office Action mailed May 10, 2006, please  
amend and reconsider the above-referenced application as follows.

Amendments to the claims begin at page 2 of this paper.

Remarks begin at page 12 of this paper.